



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

#3 *Permitta*
at least
5/1/02

In re Application of

PEI-REN JENG.

Serial No.: 09/729,833

Filed: DEC, 1, 2000

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: Group Art Unit: 2823

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: Examiner: Lynette Hsien-Ming Lee

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For: METHOD FOR PATTERNING A DUAL DAMASCENE

AMENDMENT AND RESPONSE

Honorable Commissioner for Patents

Washington, D.C. 20231

Sir:

This paper is in response to the Official Action dated January 29, 2002. In that Official Action, Claims 1-50 are rejected under 35 U.S.C. 112, second paragraph, and 35 U.S.C. 103(a); and further, Claims 10, 14, 17, 24, 27 and 29 are objected. Kindly amend and reconsider the application in accordance with the following particulars:

IN THE CLAIMS:

Claims 1 through 50 have been deleted.

Please add new claims 51 - 63 as follows:

51. A method for forming a dual damascene opening, comprising:
providing a substrate with a dielectric layer in a certain thickness thereon;

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